L Number	Hits	Search Text	DB	Time stamp
1	434086	photoresist photo-resist photosensitive photo-sensitive (sensitive near (radiation energy photo light)	USPAT; US-PGPUB; EPO; JPO;	2004/01/09 18:16
2	0	(photoresist photo-resist photosensitive photo-sensitive (sensitive near (radiation energy photo light))) same cavity same (exposs) irradiatis) same developes, same	DERHENT USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/09 18:17
4	151747	laminatS5 same membrane (cover membrane) near2 (layer film coating)	USPAT; US-PGPUB; EPO; JPO;	2004/01/09 18:27
5		(photoresist photo-resist photosensitive photo-sensitive (sensitive near (radiation energy photo light))) same (cavity channel microchannel micro-channel well microwell micro-well chamber) same laminat\$5 same membrane	DERMENT USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/09 18:21
6	4909745	(cavity channel micro-channel micro-channel well microwell micro-well chamber)	USPAT; US-PGPUB; EPO; JPO; DERMENT	2004/01/09 18:22
7	7959	(laminat85 cover\$3) with ([cover membrane] near2 (layer film coating)) with ([cavity channel micro-well channel well micro-well micro-well channer))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/09 18:27
8	345	(photoresist photo-resist photosensitive photo-sensitive (sensitive near (radiation energy photo light)) same ((laminat85 cover\$3) with ([cover membrane) near2 (layer film coating)) with ((cavity channel microchannel picro-channel well	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/09 18:24
•	35	microwell micro-well chamber)) (Iphotoresis photo-ensitive photosensitive photo-ensitive (sensitive near [rediation energy photo (lamit) near (laminate) cowered) with ((cover membrane) near2 (layer Ilm costing) with ((cavity chamber)))) and (laminate) (layer Ilm costing) with (lawity near (laminate) (lawity near (lawity)) and (lawity) (lawit	USPAT; US-PGPUB, EPO; JPO; DERMENT	2004/01/09 18:24
10	4826	205/%.ccls.) (laminat85 cover\$3) with membrane with ((cavity channel microchannel micro-channel well microwell micro-well	USPAT; US-PGPUB; EPO; JPO;	2004/01/09 18:28
11	1810	chamber]) (microfluid\$3 micro-fluid\$3 micro adj fluid\$3) adj device	DERWENT USPAT; US-PGPUB; EPO; JPO;	2004/01/09 18:28
2		((laminat\$5 cover\$3) with membrane with ((cavity channel microchannel micro-channel well microwell micro-well chamber])) and ((microfluid\$3 micro-fluid\$3 micro adj fluid\$3) adj device)	DERWENT USPAT; US-PGPUB; EPO; JPO; DERMENT	2004/01/09 18:30
5		(photoresist photo-resist photosensitive photo-sensitive (sensitive near (radiation energy photo light)) same (llaminate) cover\$3) with membrane with (cavity channel microchannel micro-channel well microwell sicro-well chamber)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/09 18:33
6	9468	(photoresist photo-resist photosensitive photo-sensitive (sensitive near (radiation energy photo light))) near first!	USPAT; US-PGPUB; EPO; JPO; DERMENT	2004/01/09 18:33

17	8493	(photoresist photo-resist photosensitive	USPAT;	2004/01/09 18:33
		photo-sensitive (sensitive near (radiation energy photo light))) near second!	US-PGPUB; EPO; JPO; DERWENT	
19	35491	photomask photo-mask photo adj mask	USPAT; US-PGPUB; EPO; JPO;	2004/01/09 18:34
22	30876	(electrode gate opaque shield\$3) near2 mask	DERWENT USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/09 18:36
23		([photoresist photo-resist photo-sensitive photo-sensitive (sensitive near (relation energy photo-sensitive (sensitive near (rest)) same ((photoresis the photo-sensitive) photo-sensitive (sensitive near (redistion energy photo-light)) near second) sense (photomask photo-mask photo adj wask) same (deactrode) gakt opaque staleld3) near)	USPAT; US-PGPUB; EPO; JPO; DERMENT	2004/01/09 18:37
24		(photoresist photo-resist photosensitive photo-sensitive (sensitive near (radiation energy photo light)) same (photomask photo-mask photo adj mask) same [[electrode gate opaque shields]] near2 mask)	USPAT; US-PGPUB; EPO; JPO; DERHENT	2004/01/09 18:37
25	59	((photoresist photo-resist photosensitive photo-sensitive (sansitive near (radiation energy photo-light)) same (photomask photo-mask photo-mask photo-sensitive same (cleatrode gate opeque shield\$3) near2 mask)) same ((cavity channel microchannel mairoro-channel mell microwell micro-well	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/09 18:41
26	699	chamber) ('photoresist photo-resist photosensitive photo-sensitive (sensitive near (radiation energy photo light)) near first!) with ((cavity channel microchannel micro-channel well microwell micro-well chamber)	USPAT; US-PGPUB; EPG; JPG; DERNENT	2004/01/09 18:41
27	741	((Photoresist Photo-resist Photosensitive Photo-sensitive (sensitive near (radiation energy photo light)) near second) with ((cavity channel microchannel micro-channel well micro-well micro-well chamber)	USPAT; US-FGPUB; EPO; JFO; DERMENT	2004/01/09 18:41
28		(electrochemical electro-chemical electro adj chemical) adj cell	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/09 18:41
29		(([photoremist photo-resist photosemality photo-sensity emergency photo-sensity ender indistion photo-sensity emergency photo-sensity ender indistion ([covity, channel.microc	USPAT; US-PGPUB; EPO; JPO; DERMENT	2004/01/09 18:42

31	37	(((microfluid\$3 micro-fluid\$3 micro adj fluid\$3) adj davice) ((electrochemical electro-chemical electro adj chemical) adj	USPAT; US-PGPUB; EPO; JPO;	2004/01/09 18:45
		cell) and ((photosesist photo-resist photosensitive photosensitive photosensitive (sensitive near (radiation energy photo light)) near first) and ((photosesist photo-resist photosensitive photosensitive photosensitive photosensitive photosensitive photosensitive) near irodation energy photo light)) near contained (carry channel microchannel energy channel microchannel contained (carry channel microchannel energy channel microchannel energy channel ener	DERWENT	
32	86		USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/09 18:45
33	126	([shotoresist photo-resist photosensitive photo-sensitive (sensitive near (radiation energy photo light)) near second() near4 ([slectrode gate opaque shield\$3) near2 mask)	USPAT; US-PGPUB; EPO; JPO; DERMENT	2004/01/09 18:46
34	0	[()photoresist photo-resist photosensitive photo-sensitive locatitive lear (radiotive near (radiotive near (radiotive near)) photo-sensitive photo-sensitive photo-sensitive and pass() photosensitive photo-sensitive (sensitive near (radiotive near photosensitive near (sensitive near (s	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/09 18:46
35	0	(()Mhotoresist photo-resist photosensitive photo-sensitive (sensitive near (reduied near () photosensitive (sensitive near (reduied near () photosensitive () near () near () near () () () () () () () () () () () () ()	USPAT; US-PGPUB; EFO; JPO; DERMENT	2004/01/09 18:48
36		(([photoresist photo-resist photosonsitive photo-sensitive (sansitive near [radiate] near [radiate] photo-sensitive (sansitive near [radiate] near state (photosonsitive photosonsitive (sansitive photosonsitive photosonsitive photosonsitive photosonsitive photosonsitive (sansitive near [radiation energy photo [light]) near (salidation energy photos [light]) near (salidation energy photosonsitive sansitive (sansitive exceed)) near (salidation energy photosonsitive near (salidation energy photosonsitive near (salidation energy photosonsitive near (salidation energy))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/09 18:47
37	0	(([photoresist photo-resist photosensitive photo-sensitive (sensitive lear (radiative lear (radiative sensitive sens	USPAT; US-PGPUB; EPO; JPO; DERMENT	2004/01/09 18:47
.8		([photoreasist photo-resist photosensitive) photo-ensistive (sensitive) near (radiative) photo-ensisty he near (radiative) energy photo-ensisty boto-ensisty photo-ensisty photo-ensisty photo-ensisty photo-ensisty photo-ensistive (ensistive near (radiation photo-ensistive (ensistive near (radiation resist)) near second) sage ((electrode light)) near second) sage (relectrode light)) resistency (electrode light) ensistency (electrode light) near second) sage (relectrode light) near (electrode light) nea	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/09 18:47

39	124196	(single one)near4 (expos\$3 irradiat\$5)	USPAT;	2004/01/03	18:49
			US-PGPUB; EPO; JPO;		
40	12	(photomask photo-mask photo add mask) same	DERWENT USPAT:	1	
10	14	((electrode gate opaque shield\$3) near2	US-PGPUB:	2004/01/09	18:53
1		mask) same ((single one near4 (expos\$3	EPO, JPO;		
	1	irradiat\$5))	DERWENT		
41	40	(photomask photo-mask photo adj mask) with	USPAT;	2004/01/09	18:51
		cover\$3 with ((electrode gate opaque shield\$3) near2 mask)	US-PGPUB;		
1		bile1093) Healz Mask)	EPO; JPO; DERMENT		
42	710	(back-side backside back adj side) adj	USPAT:	2004/01/09	10.50
		(expos\$3 irradiat\$5)	US-PGPUB:	2004/01/03	10.02
			EPO; JPO;		
43	734		DERWENT		
43	734	(photomask photo-mask photo adj mask) same ([electrode gate opaque shield\$3) near2	USPAT;	2004/01/09	18:53
		((electrode gate opaque snleids)) near/	US-PGPUB; EPO: JPO:		
		IMON)	DERWENT		
44	5	((photomask photo-mask photo adj mask)	USPAT:	2004/01/09	18:54
		same ((electrode gate opaque shield\$3)	US-PGPUB;		
		near2 mask)) same ((back-side backside	EPO; JPO;		
46		back adj side) adj (expos\$3 irradiat\$5)) ((back-side backside back adj side) adj	DERWENT USPAT:		
40	1 1	(expos\$3 irradiat\$5)) and 430/395.cols.	US-PGPUB:	2004/01/09	18:54
		(ongoods intended of) and 450/393.ccis.	EPO; JPO;		
			DERWENT	1	
-	60		USPAT;	2004/01/09	15:33
		MADOU-MARC-Jin. MADOU-MARK-Jin.	US-PGPUB;		
	i	MADOU-M-Jin.	EPO; JPO; DERMENT		
-	711108	resist photoresist photo-resist	USPAT;	2004/01/09	17.54
		photosensitive photo-sensitive (sensitive	US-PGPUB;	2004/01/05	17:34
		near (photo light energy radiation))	EPO; JPO;	1	
	11		DERNENT		
-	11	(MADOU-Min. MADOU-MARCin. MADOU-MARC-Jin. MADOU-MARK-Jin.	USPAT; US-PGPUB;	2004/01/09	15:45
		MADOU-M-Jin.) and (resist photoresist	EPO: JPO:		
		photo-resist photosensitive	DERWENT	1	
		photo-sensitive (sensitive near (photo			
		light energy radiation))) (microfluid\$3 micro-fluid\$3 micro add			
-	1010	fluid\$3) adj device	USPAT; US-PGPUB;	2004/01/09	18:28
		TIMINGS) MUS GEVICE	EPO: JPO:		
			DERMENT	1	
-	4	(("4874500") or ("4900405")).PN.	USPAT;	2004/01/09	15:46
	i i		US-PGPUB;		
			EPO; JPO;		
-	421	(resist photoresist photo-resist	USPAT:	2004/01/09	10.40
		photosensitive photo-sensitive (sensitive	US-PGPUB:	2004/01/09	10:40
		near (photo light energy radiation))) and	EFO; JPO;		
		((microfluid\$3 micro-fluid\$3 micro ad)	DERNENT		
_	34233	fluid\$3) adj device } (resist photoresist photo-resist	USPAT:		
	34233	photosensitive photo-sensitive (sensitive	USPAT; US-PGPUB:	2004/01/09	15:48
		near (photo light energy radiation))) with	EPO; JPO;		
		negative	DERWENT		
-	75	((microfluid83 micro-fluid83 micro adj	USPAT;	2004/01/09	15:49
		fluid\$3) adj device) and ((resist	US-PGPUB;		
	1 1	photoresist photo-resist photosensitive photo-sensitive (sensitive near (photo	EPO; JPO; DERMENT		
		light energy radiation()) with negative)	DECHONI		
-	96841	electrochemical electro-chemical electro	USPAT:	2004/01/09	15:52
		adj chemical	US-FGPUB;		
	1		EPO: JPO:		
			DERNENT		

	0	(((resist photoresist photo-resist	USPAT;	2004/01/09 16:0
		photosensitive photo-sensitive (sensitive near (photo light energy radiation))) with negative) same (cavity chamber)) same ((laminat\$5) with membrane)	US-PGPUB; EPO; JPO; DERWENT	
-	1153	liga!	USPAT; US-PGPUB; EPO; JPO;	2004/01/09 15:5
-	105	(microfluid\$3 micro-fluid\$3 micro adj fluid\$3) adj device) and liga!	DERWENT USPAT; US-PGPUB; EPO; JPO;	2004/01/09 15:5
	68	liga! and 430/\$.ccls.	DERMENT USPAT; US-PGPUB; EPO: JPO:	2004/01/09 16:0
	4964576	channel microchannel micro-channel cavity chamber wold well	DERWENT USPAT; US-PGPUB; EPO; JPO;	2004/01/09 16:2
	59543	(resist photoresist photo-resist photosensitive photo-sensitive (sensitive near (photo light energy radiation))) with (channel microchannel micro-channel cavity	DERWENT USPAT; US-PGPUB; EPO; JPO; DERMENT	2004/01/09 16:3
	21	chamber void well) ((resist photoresist photo-resist photosensitive photo-sensitive (sonsitive near (photo light energy radiation))) with (chennel microchannel micro-chamnel cavity chamber void well)) with cover\$3 with membrane	USPAT; US-PGPUB; EFO; JPO; DERMENT	2004/01/09 16:3
	202	memorane ((resist photoresist photo-resist photosensitive photo-sensitive (sensitive near (photo light energy radiation))) with (channel microchannel micro-channel cavity chamber void well) and (microfluid3 micro-fluid\$3 micro edj fluid\$3 adj device 1	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/09 16:3
		device; (resist photoresist photo-resist photosemsitive photo-sensitive (sensitive near (photo light energy radiation))) with (channel micro-channel cavity channer void well) with (cover\$3 membrane laminat\$5]	USPAT; US-PGPUB; EFO; JPO; DERMENT	2004/01/09 16:3
	36	(Tresist photoresist photo-resist photosensitive photosensitive photosensitive (sensitive reset photosensitive photosensitive (sensitive reset photosensite photo	USPAT; US-PGPUB; EPO; JPO; DERMENT	2004/01/09 16:4
	309	(microfluid#3 micro-fluid#3 micro adj fluid#3) adj device) with (method process step) with (form#3 formation manufactur#3 produc#5)	USPAT; US-PGPUB; EPO; JPO;	2004/01/09 16:4
	1	((microfluids) micro-fluids) micro adj fluids) adj device with [method process step) with (forms) formation manufacturs) produc\$5)) same ((rosist photoresist photo-resist photorensitive photo-sensitive (sensitive near (photo	DERWENT USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/09 16:4
	15	light energy radiation)) with negative) ((microfluid3) micro-fluid3) micro adj fruid3) adj device y sith method process step) with (form3) formation manufactur#3 produc#5)) same (resist photoresist photosensitive photo-ensist photosensitive (sensitive near (photo	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/09 16:4

	4966878		USPATI	12004/01/09 16:53
		photosensitive photo-sensitive (sensitive near (photo light energy radiation))) same membrane (channel microchannel	He-renus.	1
-	1160	micro-channel cavity chamber void well) (resist photo-resist photo-sensitive photo-sensitive (sensitive near (photo light energy radiation))) same membrane same (channel nicrochannel micro-channel cavity chamber void well)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/09 16:55
=	86	((resist photocosist photo-resist photosensitive photo-sensitive (sensitive near (photo light energy radiation))) same membrane same (channel indrochannel micro-channel cavity chamber void well)) and 430/8,cis*	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/09 17:08
-	25540	<pre>(resist photoresist photo-resist photosensitive photo-sensitive (sensitive near (photo light energy radiation))) near2 first;</pre>	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/09 17:08
-	20915	(resist photoresist photo-resist photosensitive photo-sensitive (sensitive near (photo light energy radiation))) near2 second!	USPAT; US-PGPUB; EPO; JPO; DERMENT	2004/01/09 17:09
-	3150	(back-side back adj side backside) near2 (expos\$3 irradiat\$5)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/09 17:11
		((resist photoresist photo-resist photo-resist photosensitive (sensitive near (photosensitive photosensitive near (photosensitive photosensitive near) photosensitive near (photosensitive near) furnity near (photosensitive near) photo-resist photosensitive near (photosensitive near) (photosensitive near) near (photosensitive near) near (photosensitive near) near (sexpessitive near near (expessitive near near near near near near near nea	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/09 17:12
	18	((resist photomesiat photomesiat) photomesiative (sensitive near photomesiative photomesiative (sensitive near (photo light energy radiation))) near (photo light energy radiation)) near2 [intel] same ((resist photomesiat photomesiate photomesiate photomesiate photomesiate photomesiate photomesiate near (sensitive near [second)) seme ((back-side back ad) sade backside) near2 (exposs) irradiats[s]	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/09 17:15
		(electrochemical electro-chemical electro adj chemical) mear cell	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/09 17:16
		((microfluid\$3 micro-fluid\$3 micro adj fluid\$3) adj device) ((electrochemical electro-chemical electro adj chemical) near cell)	USPAT; US-PGPUB; EPO; JPO; DERMENT	2004/01/09 17:48
		photomask photo-mask photo adj mask	USPAT; US-PGPUB; EPO; JPO; DERWENT	2004/01/09 17:19
	79461	(membrane cover) near (layer film)	USPAT; US-PGPUB; EFO; JPO; DERWENT	2004/01/09 17:20

-		(((microfluid\$3 micro-fluid\$3 micro ad)	USPAT	2004/01/09 17	. 22
		fluid\$3) add device) [[electrochemics]	US-PGPUB;	0001/01/03 11	
		electro-chemical electro adj chemical)	EPO; JPO;		
		near cell)) and ((resist photoresist	DERMENT		
		photo-resist photosensitive			
		photo-sensitive (sensitive near (photo			
	J	light energy radiation))) same (photomask	1		
	-	photo-mask photo adj mask) same ((membrane			
		cover) near (layer film)) same (channel			
		microchannel micro-channel cavity chamber void well))	i	1	
		void well))			
		((resist photoresist photo-resist	USPAT;	2004/01/09 17:	24
		photosensitive photo-sensitive (sensitive	US-PGPUB;	1	
		near (photo light energy radiation))) same	EPO; JPO;		
		(photomask photo-mask photo adj mask) same	DERMENT		
	1	((membrane cover) near (layer film)) same			
		(channel microchannel micro-channel cavity			
	29	(((microfluids3 micro-fluids3 micro ad)			
	,	fluid83) adj device) ((electrochemical	USPAT; US-PGPUR:	2004/01/09 17:	26
		electro-chemical electro adj chemical)	EPO; JPO;		
		near cell)) and ((resist photoresist	DERWENT		
		photo-resist photosensitive	DEMMENT		
	-	photo-sensitive (sensitive pear (photo-			
	i	light energy radiation))) and (photomes)		1	
		photo-mask photo adj mask) and ((membrane			
	i	(cover) near (layer film); and (channel		1	- 1
		microchannel micro-channel cavity chamber			
					- 1
	28590	(resist photoresist photo-resist	USPAT:	2004/01/09 17:	51
		photosensitive photo-sensitive (sensitive	US-PGPUB:		32
		near (photo light energy radiation))) with	EPO; JPO;		
		(develop85 etch84 form83) with (channel	DERWENT		
		microchannel micro-channel cavity chamber void well)			
	F.O.	Acid Mell)			
	30	((resist photoresist photo-resist	USPAT;	2004/01/09 17:	54
	T .	photosensitive photo-sensitive (sensitive	US-PGPUB;		- 1
		near (photo light energy radiation))) with (develop\$5 ctch\$4 form\$3) with (channel	EPO; JPO;		
	1	microchannel micro-channel cavity chamber	DERMENT		
		Void well)) same (fluid near2		1	- 1
	1	communication)			
	434086	photoresist photo-resist photosensitive	USPAT:		
		photo-sensitive (sensitive near (photo	US-PGPUB:	2004/01/09 17:	54
	İ	light energy radiation))	EPO; JPO;		
			DERMENT		- 1
	392389	(channel microchannel micro-channel cavity	USPAT:	2004/01/09 18:0	
		chamber void well) near2 (two larges)	US-PGPUB;	2004/01/09 18:1	32
	1	Small\$2 big\$4)	EPO; JPO;	Ì	- 1
	í		DERWENT		
	29	((channel microchannel micro-channel	USPAT;	2004/01/09 18:0	32
	1	cavity chamber void well) near? /rwo	US-PGPUR:	2004/01/09 18:0	23
	1	large\$1 small\$2 big\$4)) same ((remist	EPO; JPO;		
	1	photoresist photo-resist photosensition	DERWENT		
	1	photo-sensitive (sensitive pear (where			ı
	1	light energy radiation()) near? faret()			
		same ((resist photoresist photo-regist			- 1
	1 1	near (photo light energy radiation)))			
		near2 second()			- 1